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# **Application of Deep Learning in Pharmaceutical Manufacturing**

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Deadline for manuscript submissions:

closed (20 March 2024)

## **Message from the Guest Editors**

This Special Issue on "Application of Deep Learning in Pharmaceutical Manufacturing" seeks high-quality papers focusing on the most recent advances in deep learning and their applications in drug product manufacturing. Topics include, but are not limited to:

- Design of pharmaceutical formulation;
- Prediction of physicochemical properties of drug products;
- Design of innovative nanomedicine technologies and drug delivery systems;
- Product quality control;
- Process development and design of new manufacturing technologies;
- Process monitoring and control;
- Continuous manufacturing;
- Use of innovative deep learning architectures for product design or process investigation.

We hope you consider participating in this Special Issue.











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## **Message from the Editor-in-Chief**

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